

United States Patent and Trademark Office

UNITED STATES DEPARTMENT OF COMMERCE United States Patent and Trademark Office Address: COMMISSIONER FOR PATENTS

55:	COMMISSIONER LOW LY I EN 19
	P.O. Box 1450
	Alexandria, Virginia 22313-1450
	www.usnto.gov

APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO	
10/647,386	08/26/2003	Noriyoshi Shimizu	300.1123	2050	
21171	7590 08/05/2004		EXAM	EXAMINER	
STAAS & HALSEY LLP			PAREKH, NITIN		
SUITE 700 1201 NEW YO	ORK AVENUE, N.W.		ART UNIT	PAPER NUMBER	
	ON, DC 20005		2811		
			DATE MAILED: 08/05/200	4	

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)	
	10/647,386	SHIMIZU ET AL.	
Office Action Summary	Examiner	Art Unit	
α Στου, ο Ευνού του 16 3 του 16 του 16 3 του 16 του 16 3 του 16 του 16 3 του 16 του 16 3 του 16 του 16 3 του 16 του	Nitin Parekh	2811	
The MAILING DATE of this communication a Period for Reply	ppears on the cover shee	et with the correspondence add	iress
A SHORTENED STATUTORY PERIOD FOR REP THE MAILING DATE OF THIS COMMUNICATION - Extensions of time may be available under the provisions of 37 CFR after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a recent of 1 NO period for reply is specified above, the maximum statutory perions are period for reply within the set or extended period for reply will, by state Any reply received by the Office later than three months after the main earned patent term adjustment. See 37 CFR 1.704(b). Status	1. 1.136(a). In no event, however, many many many many minimum of the statutory minimum of the will apply and will expire SIX (6) to be considered to be considered to be considered to be considered to be considered.	ay a reply be timely filed of thirty (30) days will be considered timely. MONTHS from the mailing date of this corne ABANDONED (35 U.S.C. § 133).	
1)⊠ Responsive to communication(s) filed on 02	July 2004		
, ,—	nis action is non-final.	· . 52 • 200 ·	
3) Since this application is in condition for allow closed in accordance with the practice under	vance except for formal r	•	merits is
Disposition of Claims			
4) ⊠ Claim(s) 1-9 is/are pending in the application 4a) Of the above claim(s) 7-9 is/are withdraw 5) ☐ Claim(s) is/are allowed. 6) ⊠ Claim(s) 1-6 is/are rejected. 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) are subject to restriction and	n from consideration.		
Application Papers	•		
9) The specification is objected to by the Exami 10) The drawing(s) filed on 26 August 2003 is/arc Applicant may not request that any objection to the Replacement drawing sheet(s) including the correct 11) The oath or declaration is objected to by the	e: a)⊠ accepted or b)⊡ ne drawing(s) be held in ab ection is required if the drav	eyance. See 37 CFR 1.85(a). wing(s) is objected to. See 37 CF	R 1.121(d).
Priority under 35 U.S.C. § 119			-
12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority docume 2. Certified copies of the priority docume 3. Copies of the certified copies of the priority docume application from the International Bure * See the attached detailed Office action for a li	ents have been received. ents have been received riority documents have b eau (PCT Rule 17.2(a)).	in Application No. <u>Marked from the second</u> een received in this National S	
Attachment(s) 1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/C Paper No(s)/Mail Date U.S. Patent and Trademark Office	Paper (08) 5) Notice	iew Summary (PTO-413) No(s)/Mail Date e of Informal Patent Application (PTO :	-152)

800 000

٠٠٠.

Application/Control Number: 10/647,386

Art Unit: 2811

DETAILED ACTION

Election/Restriction

1. Applicant's election without traverse of Group I, claims 1-6 in Paper No. 2 is acknowledged.

Claim Rejections - 35 USC § 103

- 2. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 4. Claims 1-4 and 6 are rejected under 35 U.S.C. 103(a) as being unpatentable over Asai et al. (US Pat. 6392898) in view of Koning et al. (US Pat. 6480370).
- 5. Regarding claims 1, 4 and 6, Asai et al. disclose a semiconductor package provided with a multilayer interconnect (MLI) structure (100 in Fig. 1) for mounting a semiconductor chip (not shown in Fig. 1; see 80 in Fig. 12) numerically referenced on its top surface, wherein:
 - a topmost stacked structure of the multilayer interconnect structure includes a
 capacitor structure (metallization-158U/insulating resin 146/metallization 58U in
 Fig. 1-9), said capacitor structure having a dielectric/insulating layer comprised of

Application/Control Number: 10/647,386

Art Unit: 2811

a mixed layer of an inorganic filler and insulating resin (146 in Fig. 1-9; Col. 7, line 65- Col. 8, line 8; Col. 7-9),

- the MLI comprising a plurality/stack of the capacitor structures including those on the top and bottom surfaces of the package (see the MLI structure in Fig. 1), and
- the structure including the chip electrodes being directly connected to the chip connection pads (see 76U and 160U in Fig. 1 and 12) and further being directly connected with the top electrodes and bottom electrodes (75U and 58U/60U respectively in Fig. 1-9)

(Fig. 1-9; Fig. 12; Col. 5, line 60- Col. 12, line 25; Col. 1-12).

Asai et al. fail to teach the dielectric layer comprising a high dielectric constant filler.

Koning et al. teach using a conventional ceramic dielectric layer having a high dielectric constant filler/powder of ceramic such as barium or lead titanate having a perovskite structure to provide a high dielectric constant and the desired electrical properties for the insulating dielectric layer (Col. 5, line 2; Col. 2, line 5)

It would have been obvious to a person of ordinary skill in the art at the time invention was made to incorporate the dielectric layer comprising a high dielectric constant filler as taught by Koning et al. so that the desired electrical properties can be achieved and the device performance can be improved in Asai et al's package.

Application/Control Number: 10/647,386

Art Unit: 2811

Regarding claims 1 and 2, forming the dielectric layer do not distinguish over Asai et al. and Koning et al., because only the final product/structure is relevant, not the process of forming the dielectric layer such as "electrodepositing", "electroless plating", "spraying" or using "chemical vapor deposition (CVD)". Note that a "product by process" claim is directed to the product per se, no matter how actually made, In re Hirao, 190 USPQ 15 at 17 (footnote 3). See also In re Brown, 173 USPQ 685; In re Luck, 177 USPQ 523; In re Fessmann, 180 USPQ 324; In re Avery, 186 USPQ 161; In re Wertheim, 191 USPQ 90 (209 USPQ 554 does not deal with this issue); and In re Marrosi et al., 218 USPQ 289, all of which make it clear that it is the patentability of the final product per se which must be determined in a "product by process" claim, and not the patentability of the process, and that an old or obvious product produced by a new method is not patentable as a product, whether claimed in "product by process" claims or not. Note that applicant has the burden of proof in such cases, as the above case law makes clear. See also MPEP 706.03(e).

Regarding claims 2 and 3, Asai et al. and Koning et al. teach substantially the entire structure as applied to claim 1 above, wherein Asai et al. further teach:

the MLI structure being on top and bottom surfaces of an insulating substrate
 (see 30 in Fig. 1; Col. 8, line 38), and

 the chip electrodes being inside a region superposed with said capacitor structure in a plan view (see 76U and the capacitor structure under the chip 80 in Fig. 12).

6. Claim 5 is rejected under 35 U.S.C. 103(a) as being unpatentable over. Asai et al. (US Pat. 6392898) and Koning et al (US Pat. 6480370) as applied to claim 1 above, and further in view of Lauffer et al. (US Pat. 5796587).

Regarding claim 5, Asai et al. and Koning et al. teach substantially the entire structure as applied to claim 1 above, except the insulating resin being a polyimide resin.

Lauffer et al. teach using a dielectric resin comprising conventional resin such as a polyimide resin (Col. 3, line 46).

It would have been obvious to a person of ordinary skill in the art at the time invention was made to incorporate the polyimide resin as taught by Lauffer et al. so that the desired electrical properties can be achieved and the device processing can be simplified in Asai et al's package.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Nitin Parekh whose telephone number is 571-272-1663. The examiner can normally be reached on 09:00AM-05:30PM.

Art Unit: 2811

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Eddie Lee can be reached on 571-272-1732. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9318.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is 703-308-0956.

NP

08-02-04

Nutur Parekh

PATENT EXAMINER

TECHNOLOGY CENTER 2800